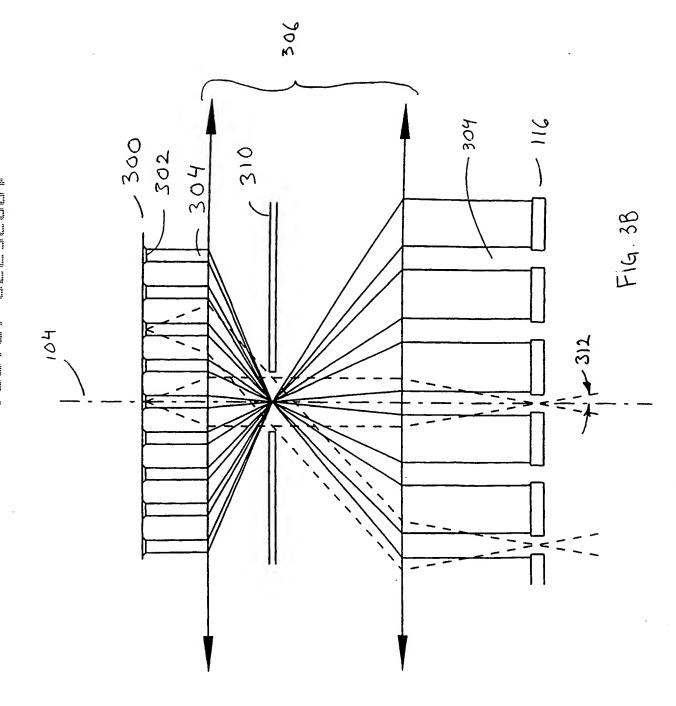
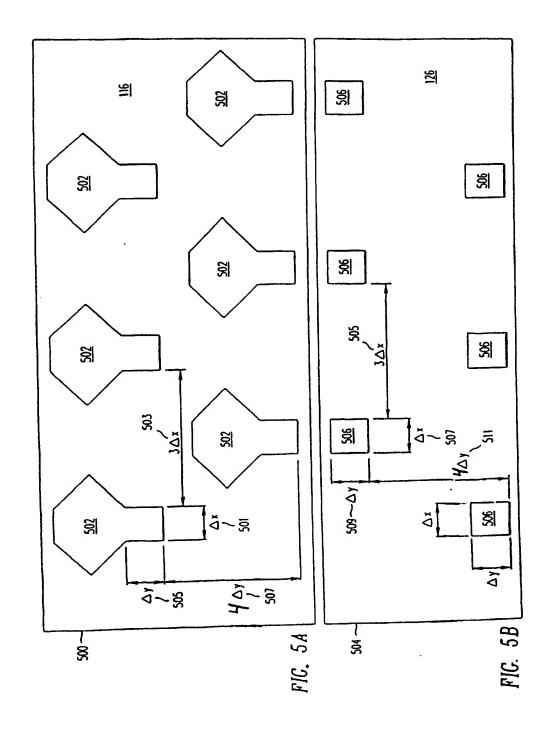
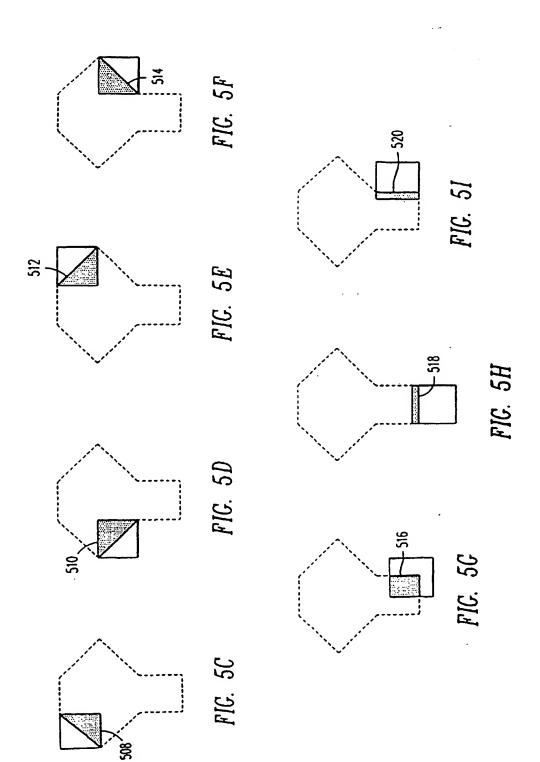


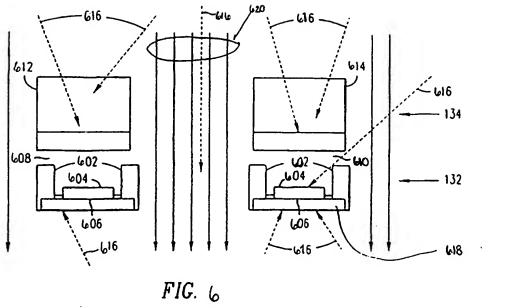
FIG. 4



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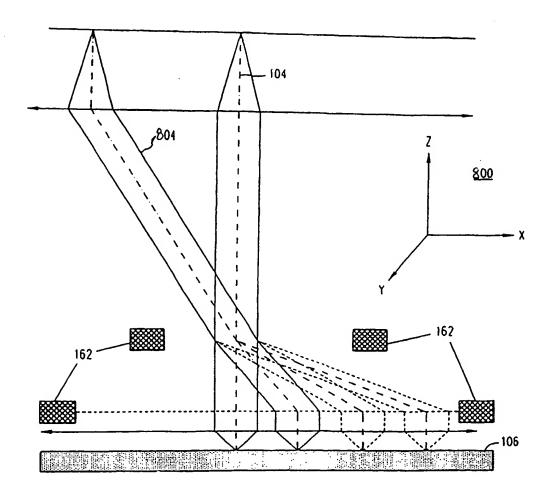
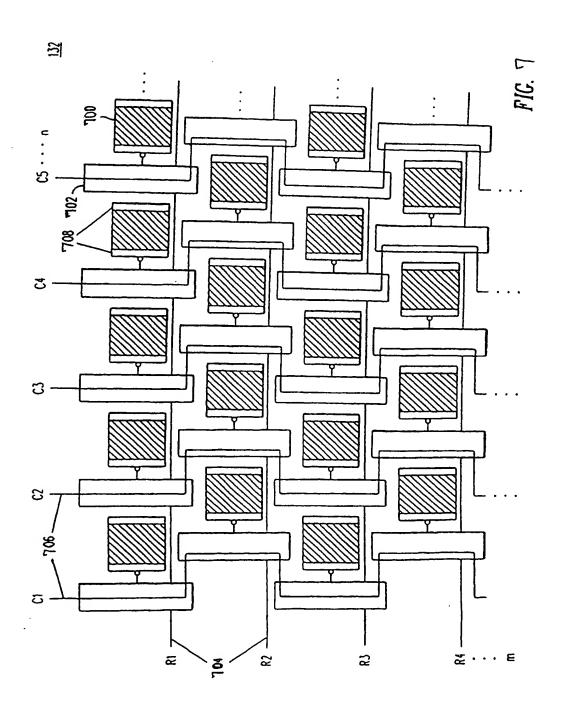
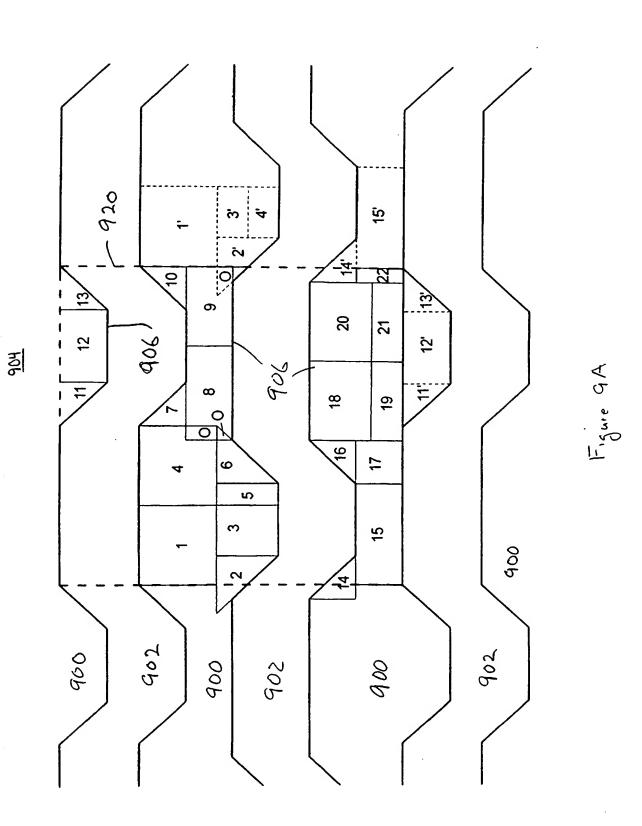


FIG. 8





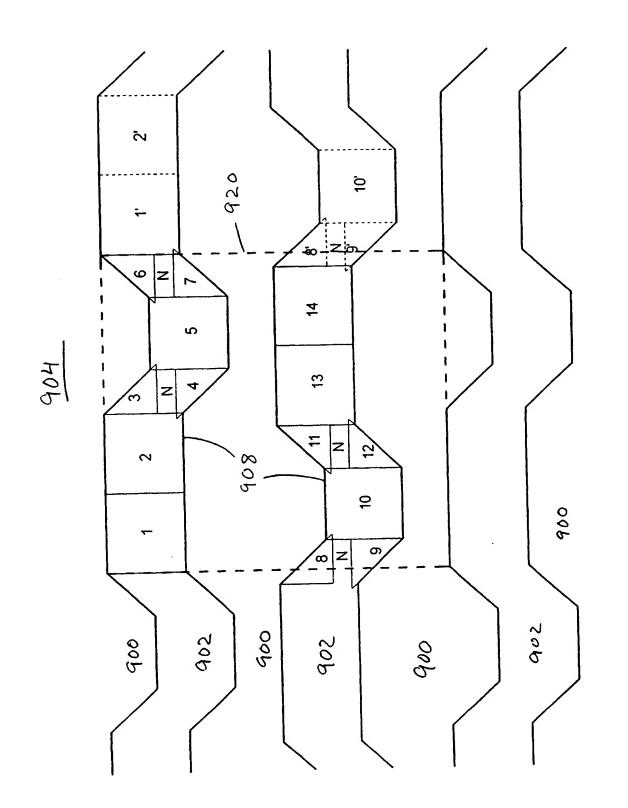
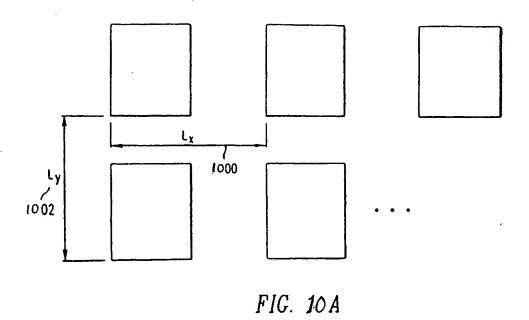
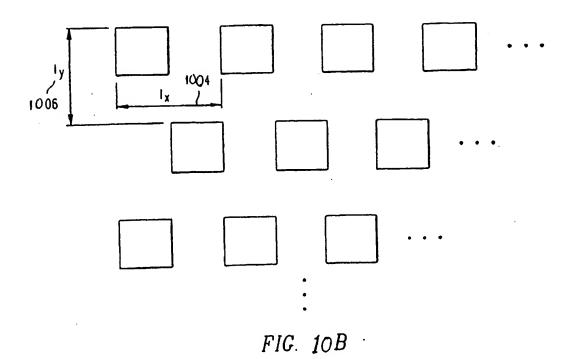
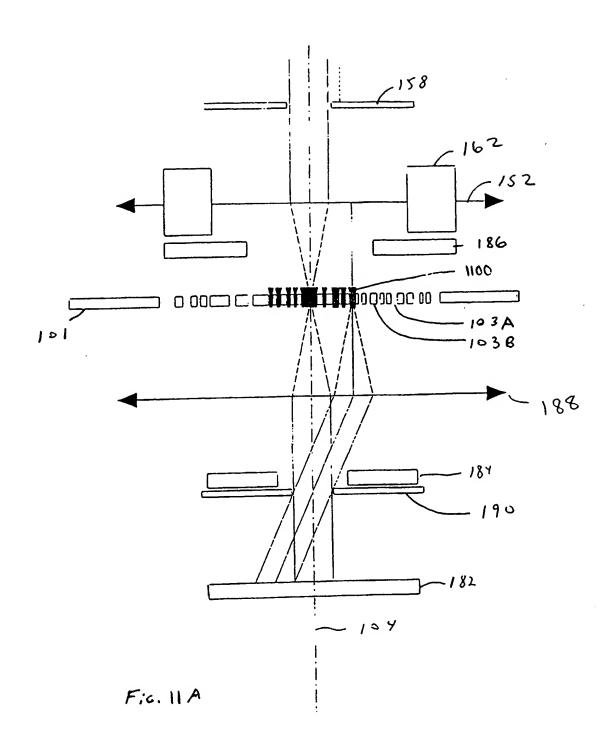
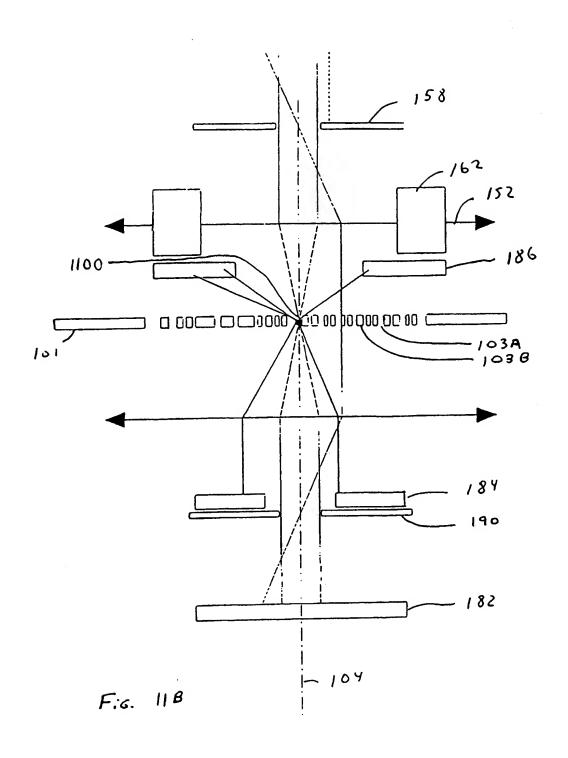


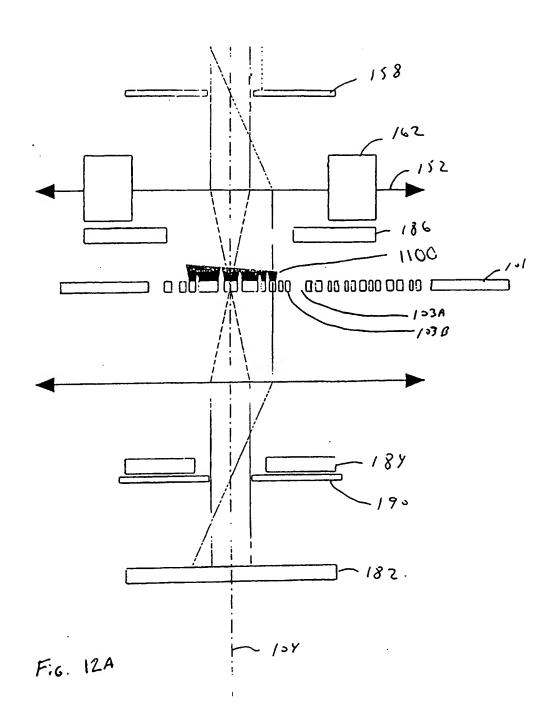
Figure 9B

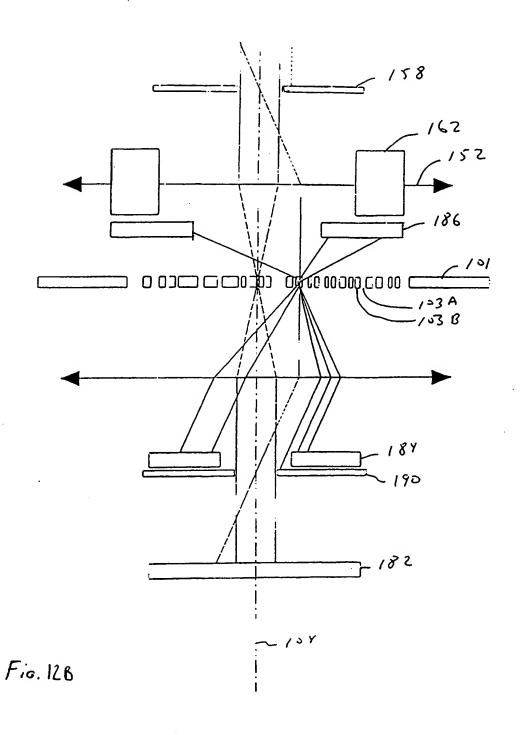


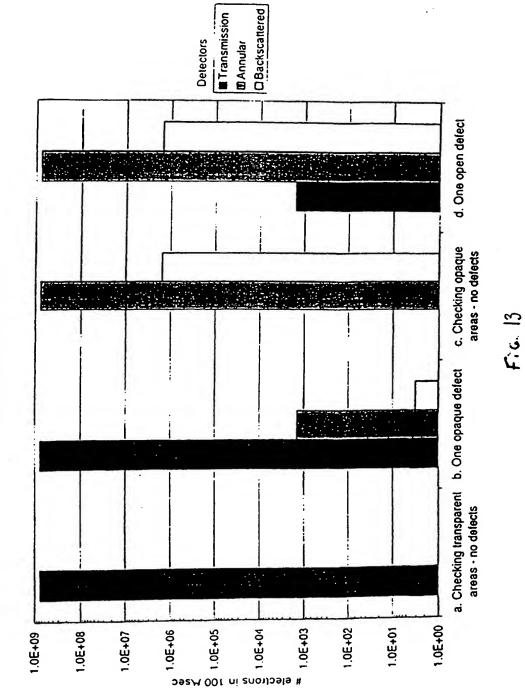




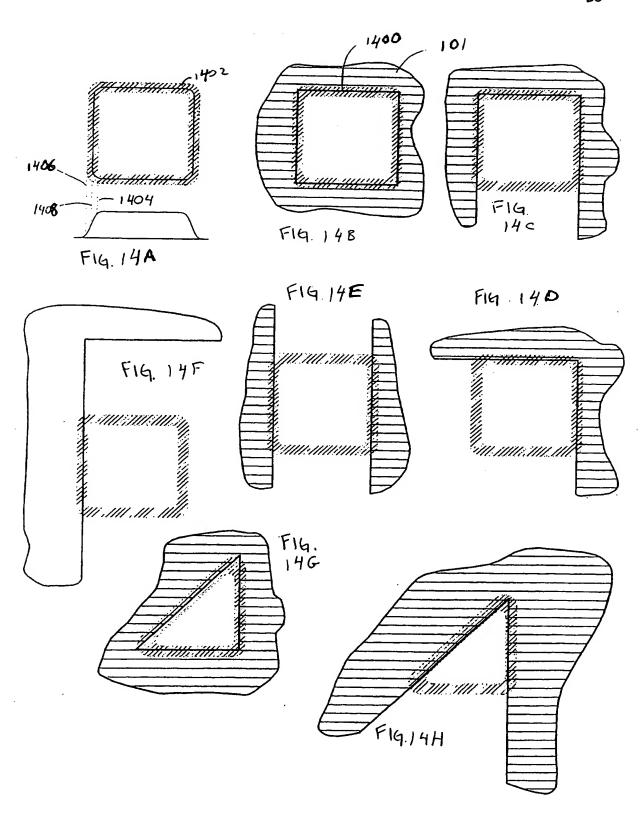


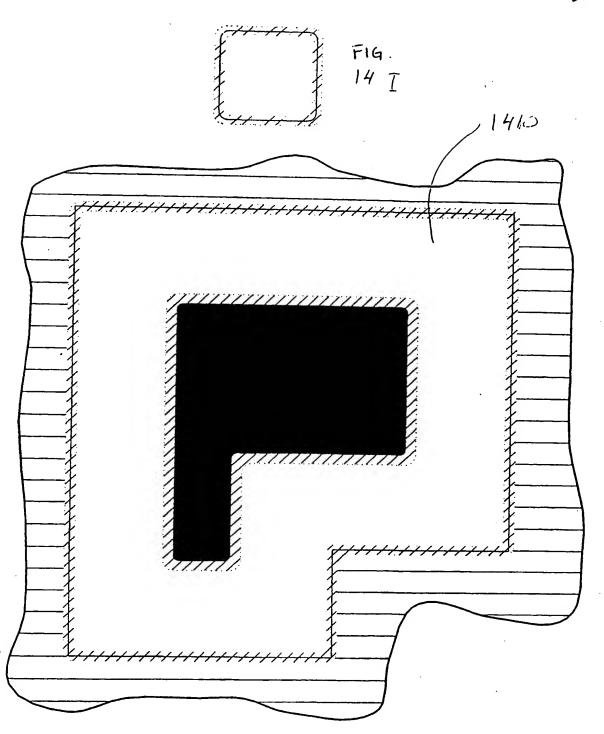






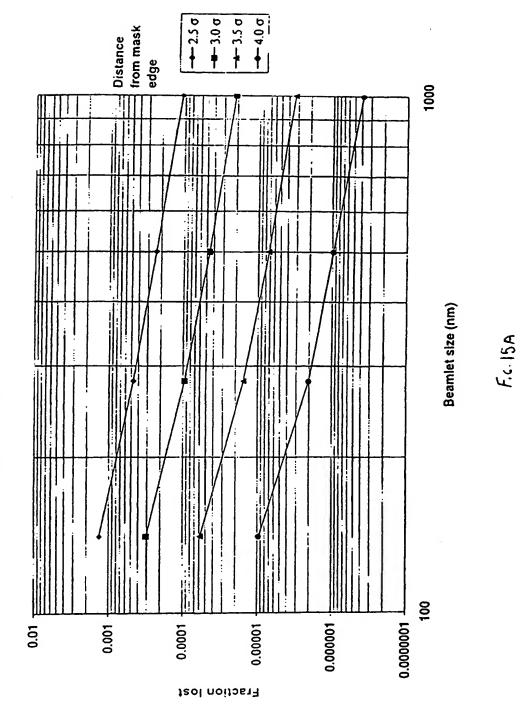
Stencil Mask Defect Detection



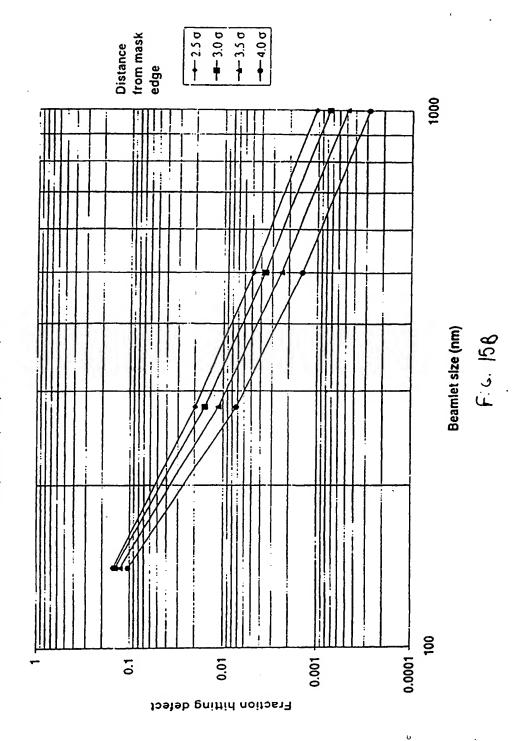


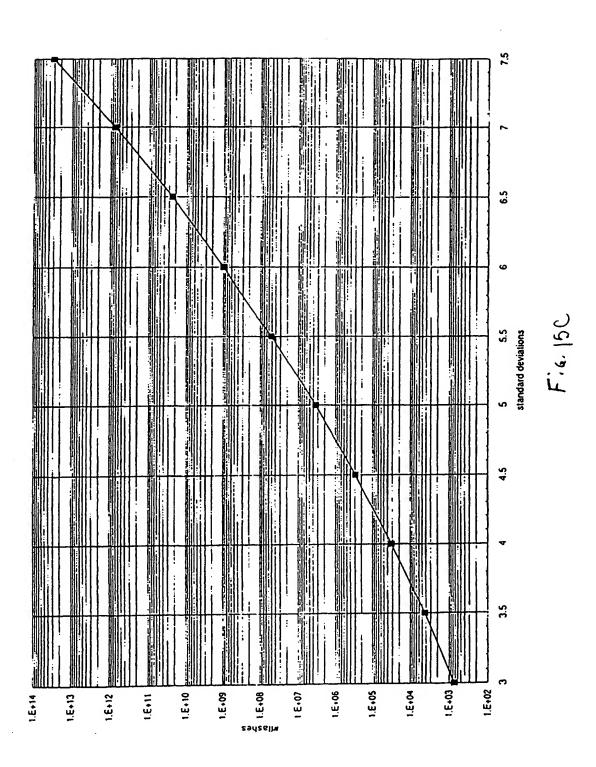
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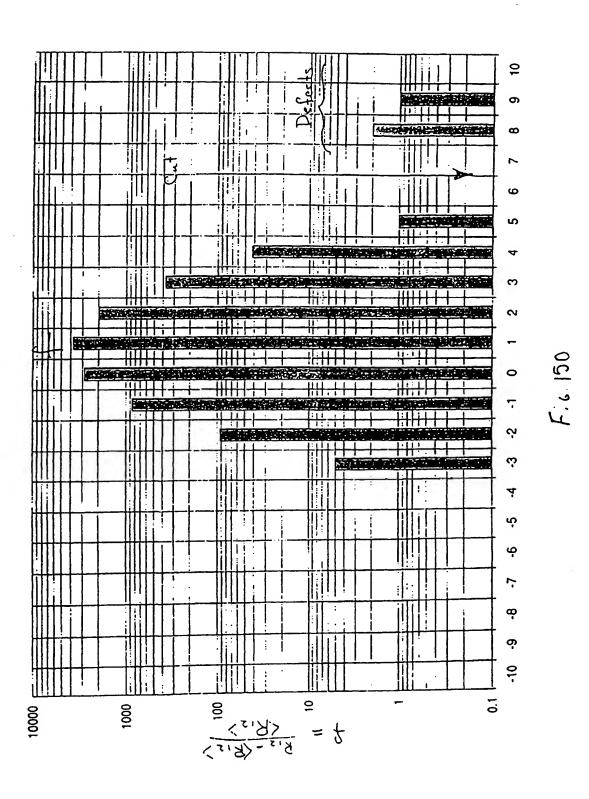
Fraction of beamlet lost on mask (on all four sides) edgewidth (12/88) = 30 nm; $1 \sigma = 12.77 \text{ nm}$



Fraction of beamlet hitting 50 nm defect edgewidth (12/88) = 30 nm; 1 s = 12.77 nm



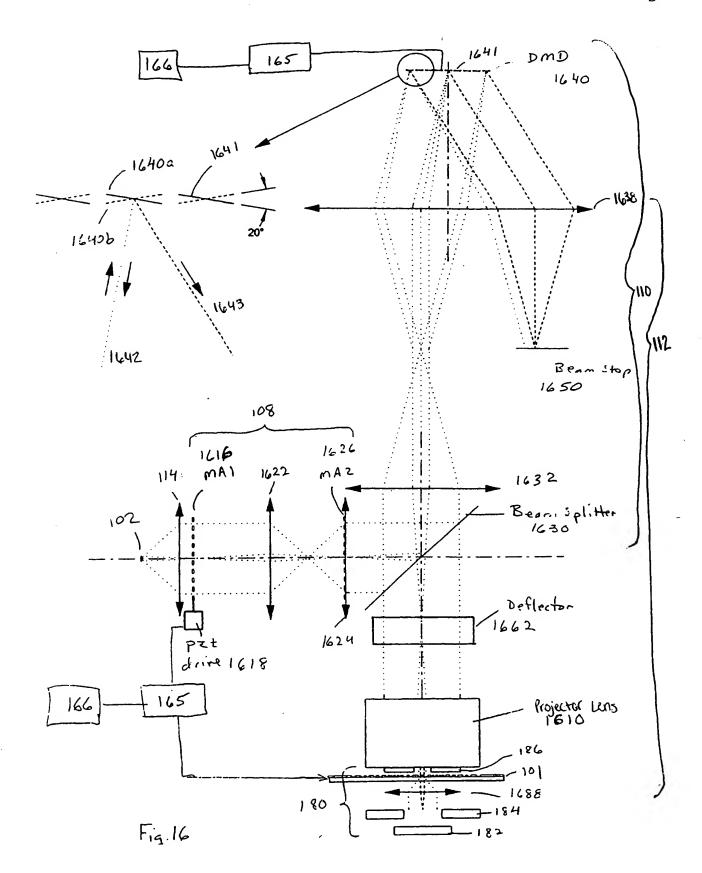


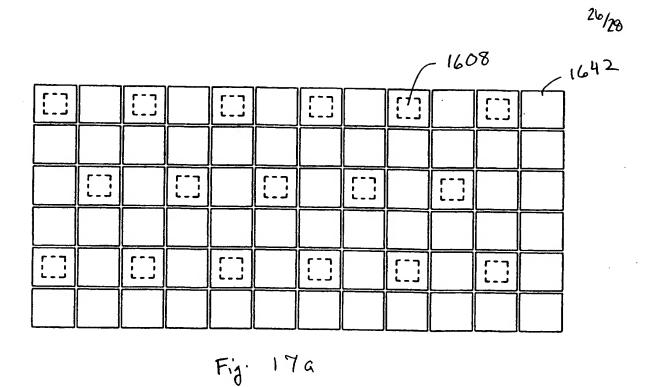


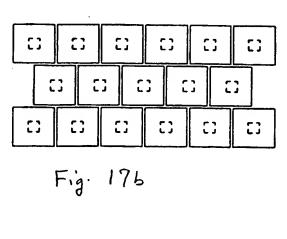
21/28 -±-50 keV f/df opaque -±-50 keV f/df clear --- 20 keV t/df opaque --- 100 keV f/df opaqu -e- 100 keV f/df clear --- 20 keV f/df clear F19 15E 0.1 0.08 Detector numerical aprture 90.0 0.04 0.02 15 9 S 25 20 0 f/df

loomays. Thisoi

f/df for clear and opaque defects







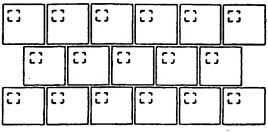


Fig. 17c

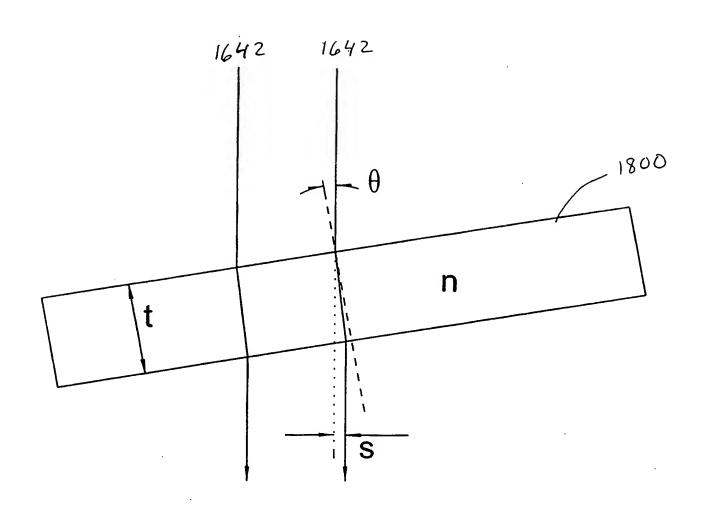


Fig. 18

